

METHOD FOR MANUFACTURING SEMICONDUCTOR STRUCTURE AND SEMICONDUCTOR STRUCTURE

ABSTRACT

Embodiments of the present disclosure belong to the technical field of semiconductor manufacturing, and involve a method for manufacturing a semiconductor structure and a semiconductor structure, which are used to improve performance of the semiconductor structure. The method for manufacturing the semiconductor structure includes: forming bit line structures on a substrate, each of the bit line structures including a conductive layer, a transition layer and a covering layer stacked sequentially, and a width of the transition layer being smaller than a width of the conductive layer; and forming air gaps on a top surface of the conductive layer and side surfaces of the transition layer. The air gaps can not only reduce influence of the covering layer on the conductive layer to prevent the resistance of the conductive layer from increasing, but also reduce the parasitic capacitance between the bit line structures and the surrounding structures thereof, thereby improving the performance of the semiconductor structure.

[Fig. 1]